

# Hafnium Oxide Deposition Parameters

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## HfO<sub>2</sub> Deposited at 110C

- 1) Heater #6 150C
- 2) Heater #7 150C
- 3) Heater #8 110C
- 4) Heater #9 110C
- 5) Heater #10 150C
- 6) Heater, Precursor1 75C Precursor= Hf(NMe<sub>2</sub>)<sub>4</sub>
- 7) N<sub>2</sub> Flow 20sccm
- 8) Pulse #0 0.015s
- 9) Wait 60s
- 10) Pulse #1 0.15s
- 11) Wait 60s
- 12) Goto 8 # of Times for required Film Thickness

(The ~Deposition Rate for this process is 0.9A/cycle)

## HfO<sub>2</sub> Deposited at 250C

- 1) Heater #6 150C
- 2) Heater #7 150C
- 3) Heater #8 250C
- 4) Heater #9 250C
- 5) Heater #10 150C
- 6) Heater, Precursor1 75C Precursor= Hf(NMe<sub>2</sub>)<sub>4</sub>
- 7) N<sub>2</sub> Flow 20sccm
- 8) Pulse #0 0.02s
- 9) Wait 10s
- 10) Pulse #1 0.3s
- 11) Wait 10s
- 12) Goto 8 # of Times for required Film Thickness

(The ~Deposition Rate for this process is 0.94A/cycle)